

IMFEDK 2011 Awards

■ IEEE EDS Kansai Chapter IMFEDK Best Paper Award

Paper ID: B-1

Titled: “Performance Improvement of Metal-Gate/High-k CMOS by NiPt-Silicidation Using Laser Annealing”

Authors: Y. Yamamoto, T. Yamaguchi, Y. Kawasaki, S. Kudo, J. Tsuchimoto, K. Sato, Y. Nishida, T. Yamashita, H. Oda, and Y. Inoue

Affiliation: Renesas Electronics Corporation

■ IEEE EDS Kansai Chapter IMFEDK Student Paper Award

Author: **Shimpei Ogiwara**

Paper ID: PA-11

Titled: “High-quality Single-crystal SiGe Layers on Insulator Formed by Rapid Melt Growth”

Coauthors: Y. Suzuki, C. Yoshimoto, T. Hosoi, T. Shimura, H. Watanabe

Affiliation: Osaka University

Author: **Yumi Kawamura**¹

Paper ID: PB-5

Titled: “Low Temperature Processed ZnO Thin Film Transistors Fabricated by Plasma Assisted Atomic Layer Deposition”

Coauthors: M. Tani¹, M. Horita^{1,2}, Y. Ishikawa^{1,2}, Y. Uraoka^{1,2}

Affiliation: ¹Nara Institute of Science and Technology, ²CREST

Author: **Tomohiro Higaki**

Paper ID: PB-9

Titled: “Flexible Zinc Oxide Thin-Film Transistors using Oxide Buffer Layers on Polyethylene Naphthalate Substrates”

Coauthors: T. Tachibana, Y. Kimura, T. Maemoto, S. Sasa, M. Inoue

Affiliation: Osaka Institute of Technology

Author: **Yasuhiro Kakihara**^{1,2}

Paper ID: PC-3

Titled: “Application of Endohedral Iron-oxide Ferritin to Resistive Memory”

Coauthors: M. Uenuma^{1,2}, N. Okamoto¹, K. Kawano^{1,2}, B. Zheng^{1,2}, Y. Ishikawa^{1,2}, I. Yamashita^{1,2}, Y. Uraoka^{1,2}

Affiliation: ¹Nara Institute of Science and Technology, ²CREST

Author: **Toshifumi Ota**

Paper ID: PC-10

Titled: “Characterization of Transient Drain Current Overshoot in Poly-Si TFTs”

Coauthors: Y. Kamakura, K. Taniguchi

Affiliation: Osaka University